

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	14	(etch\$3 same (silicon near nitride)) same (regenerat\$3 or recircuлат\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/08/24 19:50
L2	1838	(phosphoric near acid or "H.sub.3 PO.sub.4") same (regenerat\$3 or recircuлат\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/08/24 20:00
L3	4	2 same (replenish\$3 same water)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/08/24 19:52
L5	1838	((phosphoric near acid) or ("H. sub.3 PO.sub.4")) same (regenerat\$3 or recircuлат\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/08/24 20:00
L6	10	5 same ((filtrat\$4 or remov\$3) same silicon)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/08/24 20:04
L7	4	5 same (precipitat\$3 same silicon)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/08/24 20:04
L8	1068	((phosphoric near acid or "H.sub.3 PO.sub.4") same etch\$3) same (controll\$3 or maintain\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/08/24 20:05
L9	468	8 and ((remov\$3 or precipitat\$3 or filt\$7) same silicon)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/08/24 20:07
L10	0	9 and (replanish\$3 same water\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/08/24 20:07

L11	244	9 and water\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/08/24 20:08
L12	86	9 and ((add\$3 or inject\$3) same water\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/08/24 20:08
L13	48	12 and @pd<"20020917"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/08/24 20:09
S1	28	((phosphoric near acid or "H ₃ PO ₄ ") same etch\$3) same (regenerat\$3 or recirculat\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/08/24 19:36
S2	8	S1 and (remov\$3 same silicon)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/08/24 18:44
S3	2	("5470421").PN.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/08/24 18:50
S4	2	("4980017").PN.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/08/24 18:50
S5	6	((phosphoric near acid or "H ₃ PO ₄ ") same etch\$3) same (filtr\$5 same silicon)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/08/24 19:49